## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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Tyler A. Lowrey

Group Art Unit:

Serial No.:

10/634,140

Examiner:

Filed:

August 4, 2003

For:

Phase Change Access Device For

Memories

Atty. Dkt. No.:

ITO.0552US (P16160)

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

## INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Applicant submits the references listed on the attached form PTO 1449 together with any required copies of such references.

This statement is being filed within three months of the filing date of the application. Please apply any charges or credits to Deposit Account No. 20-1504.

Respectfully submitted,

Date: 16/30/03

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Date of Deposit: I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

Sherry Tipton

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